Contents

Preface v

Publication schedule vii

Contents ix

Committees xiii

Exhibitors xviii

COATINGS FOR USE AT HIGH TEMPERATURES

Coatings to resist high-temperature corrosion

Effect of substrate composition on the oxidation behavior of platinum-aluminized nickel-base superalloys 1
H. M. Tawancy, N. M. Abbas (Dharhan, Saudi Arabia) and T. N. Rhys-Jones (Bristol, UK)

Microstructural development in aluminide diffusion coatings on nickel-base superalloy single crystals 8
W. F. Gale and J. E. King (Cambridge, UK)

Increasing high temperature oxidation and corrosion resistance of graphite and carbon-fiber-reinforced carbon by deposition of a low pressure chemically vapor-deposited silicon carbide coating 13
J. H. Scheiffarth, B. J. Wagner (Menomonee Falls, WI, USA), K. Brennfleck and W. Huettner (Giessen, Germany)

Vacuum plasma sprayed alumina–titania coatings 19
D. J. Varacalle, Jr. (Idaho Falls, ID, USA), H. Herman, G. A. Bancke (Stony Brook, NY, USA) and W. L. Riggs II (Loveland, OH, USA)

Coatings to resist wear at high temperatures

Erosive wear of CVD ceramic coatings exposed to particulate flow 25
V. Shanov, W. Tabakoff and M. Metwally (Cincinatti, OH, USA)

The influence of erodent characteristics on the erosion of selected coatings at ambient and elevated temperature 32
P. N. Walsh and R. C. Tucker, Jr. (Indianapolis, IN, USA)

Evaluation of plasma sprayed abradable coatings 39
Z. Mutasim, L. Hsu and E. Wong (San Diego, CA, USA)

Thermal barrier coatings

Thermomechanical behavior and phase relationships of plasma-sprayed zirconia coatings 45
M. P. Borom and C. A. Johnson (Schenectady, NY, USA)

Thermal properties and microstructure of two thermal barrier coatings 53
T. A. Taylor (Indianapolis, IN, USA)

Compositionally graded thermal barrier coatings for high temperature aero gas turbine components 58
F. Jamarani, M. Korotkin, R. V. Lang, M. F. Ouellette, K. L. Yan, R. W. Bertram (Whitby, Ont., Canada) and V. R. Parameswaran (Ottawa, Ont., Canada)

The effect of residual stress on martensitic transformation in plasma-sprayed ZrO_2 (8 wt.%Y_2O_3) coatings 64
J. D. Lee, H. Y. Ra, K. T. Hong and S. K. Hur (Seoul, South Korea)

Acoustic emission study of failure mechanisms in TiC thermal barrier coatings 70
F. Bordeaux (St. Martin d'Hères, France), C. Moreau (Boucherville, Que., Canada) and R. G. Saint Jacques (Varennes, Que., Canada)

Coatings for composites used at high temperature

TiN films as microlaminate reinforcements in aluminum matrix composites 77
J. H. Givens (Essex Junction, VT, USA) and J. M. Rigsbee (Urbana, IL, USA)

Coatings for use at high temperatures (poster session)

Microstructure and resistance to cracking of modified Al–Si and Al–Cr diffusion coatings on ŻS6K nickel-based superalloys 84
L. Swadźba, A. Maciejny, B. Formanek (Graniczna, Poland) and J. Biedroń (Hetmańska, Poland)

HARD COATINGS AND VAPOR DEPOSITION TECHNOLOGY

PVD technology I: Plasma and magnetic field characterizations

Low pressure r.f. plasma jet—a new tool for surface processing 91
L. Bárdoš and S. Berg (Uppsala, Sweden)

The use of ion effects on the surface in deposition and etching of thin films and coatings 96
G. Kuznetsov and V. Delian (Moscow, Russian Federation)

PVD technology II: Material and corrosion properties

A new technique for testing the impact load of thin films: the coating impact test 102
O. Knotek, B. Bosserhoff, A. Schrey, T. Leyendecker, O. Lemmer and S. Esser (Aachen, Germany)

Corrosion studies with hard coating–substrate systems 108
H. A. Jehn and M. E. Baumgärtner (Schwäbisch Gmünd, Germany)
Preparation and characterization of V–N films deposited by reactive triode magnetron sputtering 115
G. Farges, E. Beauprez and D. Degout (Arcueil, France)

PVD technology III: Sputter, arc, and hybrid methods

Recent progress in the study of physically vapour-deposited coatings produced by means of highly ionized plasmas 121
L. M. M. Stals, C. Quaeyhaegens and M. Van Stappen (Diepenbeek, Belgium)
Sputter erosion amplification 131
S. Berg, A. M. Barklund, C. Nender, I. V. Katardjiev and H. Barankova (Uppsala, Sweden)
The deposition of thin films by filtered arc evaporation 136
P. J. Martin, R. P. Netterfield, A. Bendavid and T. J. Kinder (Sydney, NSW, Australia)
Planar magnetron-sputtering system with obliquely facing targets 143
K. Tominaga, H. Imai, Y. Sueyoshi and M. Shirai (Tokushima, Japan)
Deposition of ternary hard compounds with a graded composition by the use of a hybrid source ion-plating technique 148
H. Freller, H.-P. Lorenz and P. Schack (Erlangen, Germany)

PVD technology IV: Residual stress and metal cutting

X-ray elastic constants and residual stress of textured titanium nitride coating 154
J. A. Sue (Indianapolis, IN, USA)
Examination of residual stress, morphology and mechanical properties of sputtered TiN films 160
F. Höhl, H.-R. Stock and P. Mayr (Bremen, Germany)
Effect of process parameters on the residual stresses and the wear behavior of aluminum nitride physical vapor deposition coatings . . . 167
G. Kleer, R. Kassner, E.-M. Meyer, M. G. Schinker and W. Doell (Freiburg, Germany)
Residual stress in ion-assisted coatings 173
S. J. Bull, A. M. Jones and A. R. McCabe (Didcot, UK)

CVD technology I: Hard coatings

On the residual stress and picostructure of titanium nitride films I: Implantation with argon or krypton 180
A. J. Perry (Boulder, CO, USA), V. Valvoda, D. Rafaja (Prague, Czechoslovakia), D. L. Williamson (Golden, CO, USA) and B. D. Sartwell (Washington, DC, USA)
Microstructural study of the κ-$Al_2O_3 \rightarrow \alpha$-$Al_2O_3$ transformation in CVD κ-Al_2O_3 186
J. Skogsmo, M. Halvarsson (Gothenburg, Sweden) and S. Vuorinen (Fagersta, Sweden)
Deposition of multilayer hard coatings using kinetically controlled chemical vapour deposition processes 193
K. Bartsch, A. Leonhardt and E. Wolf (Dresden, Germany)
Reactor design for chemical vapor deposition of tungsten carbide coatings 198
D. Garg (Allentown, PA, USA) and C. M. Kelly (Villanova, PA, USA)

CVD technology II: OMCVD and fluidized bed CVD

Assessment of tetra-alkylchromium compounds for low temperature organo-metallic chemical vapour deposition of Cr-based coatings . 204
F. Maury (Toulouse, France), F. Ossola (Padua, Italy) and F. Schuster (Toulouse, France)
Fundamental aspects of film nucleation and growth in chemical vapor deposition 211
W. A. Tiller (Stanford, CA, USA)
Chemical vapor deposition in fluidized bed reactors 219
A. Sanjurjo, K. Lau and B. Wood (Menlo Park, CA, USA)
Coatings for corrosion protection of steel used in reinforced concrete 224
A. Sanjurjo, S. Hettiarachchi, K. H. Lau, P. Cox and B. Wood (Menlo Park, CA, USA)
Low pressure chemical vapor deposition of massive $Si_{1-x}Ge_x$ gradient crystals and applications in short-wavelength diffraction 229
R. Madar, E. Mastromatteo (St. Martin d'Hères, France), A. Magerl, K.-D. Liss (Grenoble, France) and C. Bernard (St. Martin d'Hères, France)
Aluminum and alumina coatings on copper by chemical vapor deposition in fluidized bed reactors 234
K. H. Lau, A. Sanjurjo and B. J. Wood (Menlo Park, CA, USA)

PVD technology V: Multilayer and multicomponent coatings

Multicomponent and multilayer physically vapour deposited coatings for cutting tools 241
O. Knotek, F. Löffler and G. Krämer (Aachen, Germany)
Arc-evaporated Ti–V–N thin films 249
O. Knotek (Aachen, Germany), W. Burgmer (Bergisch Gladbach, Germany) and C. Stoessel (Aachen, Germany)
Ti–B–N coatings deposited by magnetron arc evaporation 255
M. Tamura and H. Kubo (Kanagawa, Japan)
Crystal structure of molybdenum nitride films made by reactive cathodic arc evaporation 261
A. J. Perry, A. W. Baouchi, J. H. Petersen and S. D. Pozder (Boulder, CO, USA)
Microstructural and tribological study of triode magnetron sputtered V–C coatings: influence of partial pressure of reactive gas 266
M. C. Sainte-Catherine and G. Farges (Arcueil, France)

Decorative properties and chemical composition of hard coatings 273
G. Reiners, H. Hantsche (Berlin, Germany), H. A. Jehn (Schwäbisch-Gmünd, Germany), U. Kopacz and A. Rack (Hanau, Germany)

PVD technology VI: Alternative approaches

Interface study of physically vapour-deposited TiN coatings on plasma-nitrided tool steel surfaces with Auger electron spectroscopy, resonant nuclear reaction analysis and Rutherford backscattering spectroscopy 279
C. Quaeyhaegens, M. Van Stappen, L. M. Stals (Diepenbeek, Belgium), F. Bodart, G. Terwagne (Namur, Belgium) and R. Vlaeminck (Gent, Belgium)
Growth and properties of hard coatings prepared by physical vapor deposition methods 287
S. Kadlec, J. Musil and J. Vyskočil (Prague, Czechoslovakia)
The coating of internal surfaces by PVD techniques 297
J. A. Sheward (Sevenoaks, UK)
High resistivity AlO_x thin films deposited by a novel two-step sputtering process 303
S. Tokumaru and M. Hashimoto (Kawasaki, Japan)
Sputtered yttria partially stabilized zirconia layers applied to thin film heat fluxmeters 308
J. C. Godefroy, M. Cléry, C. Diot, P. Kayser and C. Gageant (Châtillon, France)

PVD technology VII: Metallic films

Impurities in ion plated chromium films 315
J. H. Hsieh (Argonne, IL, USA) and R. F. Hochman (Atlanta, GA, USA)
Sputtered silver and Cr–C films for applications as interconnect materials 320
N. Maréchal, Y. Pauleau and S. Païdassi (Grenoble, France)
Structure and mechanical properties of hard W–C coatings deposited by reactive magnetron sputtering 324
Y. Pauleau, Ph. Gouy-Pailler and S. Païdassi (Grenoble, France)

Hard coatings and vapor deposition technology (poster session)

Sputter deposition of decorative coatings based on ZrB_2 and ZrB_{12} 329
C. Mitterer, P. Losbichler (Leoben, Austria), W. S. M. Werner, H. Störi (Vienna, Austria) and J. Barounig (Linz, Austria)
Ion-beam deposition of Zr–Al multilayers and their structural properties 335
S. B. Qadri, C. Kim, M. Twigg and D. Moon (Washington, DC, USA)
Fundamental mechanisms of titanium nitride formation by d.c. magnetron sputtering 338
F. Richter, H. Kupfer, H. Giegengack, G. Schaarschmidt, F. Scholze, F. Elstner and G. Hecht (Chemnitz, Germany)
Thin film deposition techniques utilizing the anodic vacuum arc 343
S. Meassick, C. Chan and R. Allen (Boston, MA, USA)
Working gas pressure and flow effects on reactively sputtered molybdenum oxide thin films 349
A. F. Jankowski and L. R. Schrawyer (Livermore, CA, USA)